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				Application Number			
				Filing Date		August 6, 2001	
				First Named Inventor		Masayuki ENDO et al.	
				Group Art Unit			
				Examiner Name			
				Attorney Docket Number		740819-595	
Sheet	1	of	1				

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U.S. PATENT DOCUMENTS							
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		Office <sup>3</sup>	Number <sup>4</sup> (if known)					
LN		Japan	07-153662	Toshihiko	06/16/1995			Abstract

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
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LN		R.R. Kunz et al., "Outgassing of organic vapors from 193 nm photoresists: Impact on atmospheric purity near the lens optics", J. Vac. Sci. Technol., B 17(6), pp. 3330-3334, Nov/Dec 1999.	
LN		H.C. Pfeiffer et al., "Projection exposure with variable axis immersion lenses: Next generation lithography", J. Vac. Sci. Technol., B 17(6), pp. 2840-2846, Nov/Dec 1999.	

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